



Fig. 3

RECEIVE RAW SPECTRAL DATA
REPRESENTATIVE OF THE CONTENT OF A
PLURALITY OF VOLATILES DESORBED
FROM A WAFER

420

410

PROCESS THE RAW SPECTRAL DATA
TO DETERMINE THE PRESENCE OF A
RESIDUAL MATERIAL ON THE
WAFER

430

CONTROL A PROCESS FLOW OPERATION
TO REDUCE THE AMOUNT OF THE
RESIDUAL MATERIAL ON THE WAFER
RESPONSIVE TO THE RESULTS OF
PROCESSING THE RAW SPECTRAL DATA

FIG. 4

